

Figure 1. DSC of (a) **3** and (b) **4**.

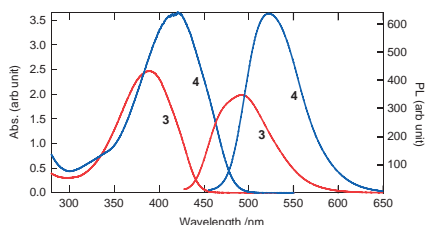


Figure 2. Absorption and PL Spectra of **3** and **4**.

stability of LC phases. A similar stability of LC phases has been observed in cyano biphenyl LC compounds.

Cyclic voltammetry of **3** exhibits two reversible oxidation waves at  $E_{1/2} = 1.22$  and  $1.47$  V (vs. Ag/AgCl in PhCN), and one reversible reduction wave at  $E_{1/2} = -0.94$  V. Compound **4** also shows two reversible oxidation waves at  $E_{1/2} = 1.03$  and  $1.22$  V, and one reversible reduction wave at  $E_{1/2} = -0.94$  V. Redox potentials of **2** have been reported to be  $E_{1/2} = 1.50$  V for oxidation, and  $E_{1/2} = -1.41$  V for reduction (vs SCE).<sup>10</sup> These results indicate that the energy gaps are 2.16, 1.97, and 2.91 eV for **3**, **4**, and **2**, respectively. In comparison with those of unsubstituted terthiophene and quaterthiophene (2.47 and 2.21 eV),<sup>11</sup> addition of a cyano group to one end of oligothiophenes reduces the energy gap, while the substitution to the both ends enlarges the energy gap.

Absorption and PL spectra of these materials measured in  $\text{CCl}_4$  are shown in Figure 2. The absorption maxima are observed at 390 and 421 nm for **3** and **4**, respectively. The cyano group of **3** induces a bathochromic shift of 35 nm relative to the unsubstituted terthiophene **5** (355 nm), whereas the absorption maximum of **3** is not much different from that of the dicyano analog **2** (385 nm).<sup>3</sup> The PL maxima are 481 and 513 nm. HOMO–LUMO gaps of **3** and **4** obtained from the absorption edges are 2.79 and 2.55 eV, respectively, in consistent with the CV results.

AFM images and XRD patterns of thin films of **4** formed on  $\text{SiO}_2$  substrates at rt and  $80^\circ\text{C}$  by vacuum deposition are shown in Figure 3. Improvement of thin-film morphology is observed with increasing the substrate temperature. In particular, screw dislocation appears in the AFM image for the thin film deposited at  $80^\circ\text{C}$ . The step size observed in Figure 3(b) is estimated to be 2.6 nm. The step size is in good agreement with the layer thickness evaluated from the XRD peaks, 2.54 nm. Since the molecular length is 2.55 nm, this indicates that the oligothiophene molecules are standing almost perpendicular to the substrate with the tilt angle of  $5^\circ$ .

Unfortunately, these compounds have not worked as organic transistors, but show anomalous transport properties in the time-of-flight measurements; ionic conduction for **3** and non ionic

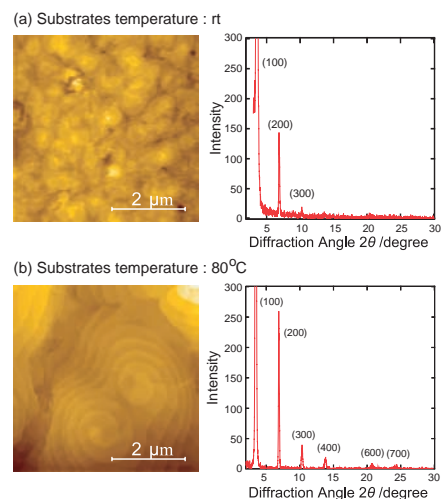


Figure 3. AFM images and XRD patterns of thin-film **4**.

conduction for **4**.<sup>12</sup>

In conclusion, we have prepared  $\alpha$ ,  $\omega$ -cyano-hexyl-terthiophene and quaterthiophene. These compounds have liquid-crystalline phases, and form good thin films on  $\text{SiO}_2$ , where the molecules are almost perpendicular to the substrates.

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